

Research Article

Electrostatic Potential Distribution Analysis of Silicon Nanowire Field Effect Transistor with Various Channel Length

Umapathi Krishnamoorthy ¹, Ravi Samikannu ², Mahesh Nataraj ³,
I. Sri Phani Sushma ⁴, Saurabh Gupta ⁵, Sathish Kumar Shanmugam ⁶,
and Narasimha Rao Dasari ⁷

¹Department of Electrical and Electronics Engineering, M. Kumarasamy College of Engineering, Karur, India

²Department of Electrical Computer and Telecommunications Engineering, Faculty of Engineering and Technology, Botswana International University of Science and Technology, Private Bag -16, Palapye, Botswana

³Department of Electronics and Instrumentation Engineering, Kongu Engineering College, Perundurai, Erode, India

⁴Department of Mechanical Engineering, Jawaharlal Nehru Technological University Kakinada, University College of Engineering, Narasaraopet, India

⁵Department of Electrical and Electronics Engineering, Technocrats Institute of Technology and Science, Bhopal, India

⁶Department of Electrical and Electronics Engineering, M. Kumarasamy College of Engineering, Karur, Tamilnadu, India

⁷Department of Electrical Power Engineering, Defence University, College Of Engineering, Ethiopia

Correspondence should be addressed to Narasimha Rao Dasari; dasari.narasimha@dec.edu.et

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Silicon nanowire FET plays a vital role in building of nanoscale electronic device applications. In this article, the silicon nanowire field effect model is designed with different channel lengths. By using the SiNW FET device model, various electrostatic potential distribution studies are done. This SiNW FET model is reducing the complexity in design. Two types of the device geometries are studied by changing the silicon nanowire channel length as 1000 nm and 200 nm. The 1000 nm channel provides high penetration to the active region of the nanowire FET than the 200 nm channel. This silicon nanowire FET model can apply to many nanoscale biochemical elements sensing applications.

1. Introduction

In nanomaterials, one-dimensional nanostructures play a great role in the detection of biochemical elements due to their excellent sensitivity at the nanoscale level. Nanowires provide high surface to volume ratio for getting great sensitivity with the conduction pathways being very small [1, 2]. So, it can cross the level of the detection limits of planar ISFETs. Due to their higher surface to volume ratio and the efficient gate filed penetration, the backgated nanowire FET shows the higher transconductance 4-10 times above the classical standard ISFETs [3]. When using ISFET for bio-

logical sensing applications, the liquid environment also works as a local gate electric field. These changes in the field vary the surface potential that produces conductance changes in the channel. Compared to the planar ISFETs, the surface potential highly influences the conduction channel of nanowires. In general, single crystalline silicon nanowires are used with p- or n-type doping in conduction channel that creates charge carriers attracted or repelled by the attached charged biological element.

In the present study, the undoped silicon nanowire is used [4, 5]. It works with the Schottky barrier FET [6, 7]. The dopant-free single crystalline silicon nanowire is free